

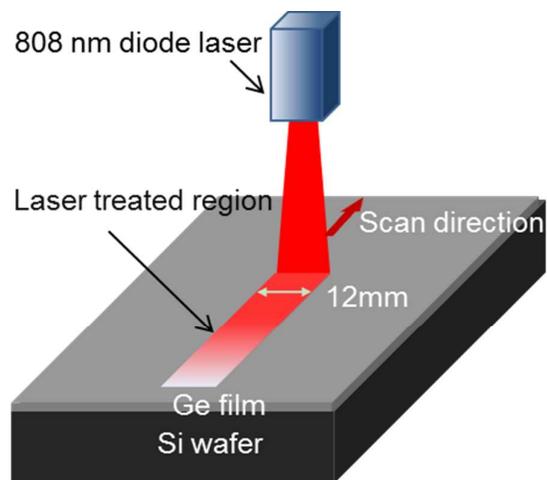
Supporting Information

**Reduction of Threading Dislocation Density in Sputtered Ge/Si (100) Epitaxial Films by Continuous-Wave Diode Laser Induced Recrystallization**

*Ziheng Liu\**, *Xiaojing Hao*, *Jialiang Huang*, *Anita Ho-Baillie*, and *Martin A. Green*

School of Photovoltaic and Renewable Energy Engineering, University of New South Wales,  
Sydney, NSW 2052, Australia

\*Corresponding Author E-mail: [ziheng.liu@unsw.edu.au](mailto:ziheng.liu@unsw.edu.au)



**Figure S1.** Schematic diagram of the diode laser annealing process